

We Claim:

1. A photoresist composition comprising a polymer comprising at least one polycyclic olefin derived type of repeat unit having a desired exo mole percent.
2. A method of improving the imaging capability of a photoresist composition, comprising providing a polymeric resin comprising polycyclic olefin derived repeat units having a desired exo mole percent.
3. A method of controlling the differential dissolution rate of a photoresist composition comprising providing a polymeric resin to the photoresist composition comprising polycyclic olefin derived repeat units having a desired exo mole percent.